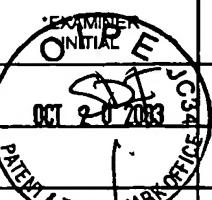


FORM PTO 1449 (modified)			ATTY DOCKET NO. <b>BHT/3230-56</b>	APPLICATION NO. <b>10/601,701</b>			
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			APPLICANT <b>YEH</b>				
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)							
Date Submitted to PTO: <b>October 20, 2003</b>			FILING DATE <b>Jun 24, 2003</b>	GROUP <b>2812</b>			
U.S. PATENT DOCUMENTS							
EXAMINER INITIALS <i>SDS</i>		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		<b>4,330,363</b>	<b>05/18/82</b>	<b>Biegesen et al.</b>			
		<b>4,592,799</b>	<b>06/03/86</b>	<b>Hayafuji</b>			
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		<b>6,495,405 B2</b>	<b>12/17/02</b>	<b>Voutsas et al.</b>			
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT	
<i>(The entire row is crossed out with a large X.)</i>							
<i>(The entire row is crossed out with a large X.)</i>							
<i>(The entire row is crossed out with a large X.)</i>							
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>SDS</i>	<b>High-Performance Low-Temperature Poly-Si TFTs Crystallized by Excimer Laser with Recessed-Channel Structure, Lin et al., IEEE Electron Device Letters, Vol. 22, No. 6, June 2001, pages 269-271</b>						
<i>1</i>	<b>Performance Improvement Obtained for Thin-Fil Transistors Fabricated in Prepatterned Laser-Recrystallized Polysilicon, Giust et al., IEEE Electron Device Letters, Vol. 18, No. 6, June 1997, pages 296-298</b>						
	<b>Comparison of excimer laser recytstallized prepatterned and unpatterned silicon films on SiO<sub>2</sub>, Giust et al., J.Appl.Phys. 81(3), 1 February 1997, pages 1204-1211</b>						
	<b>High-Performance Single Crystalline-Silicon TFTs on a Non-Alkali Glass Substrate, Sano et al. Fujitsu Laboratories Ltd., Atsugi 243-0197, Japan (C) 2002 IEEE</b>						
EXAMINER	<i>Janetta Lasee</i>			DATE CONSIDERED		<i>12/09/04</i>	

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.